## EE 240B – Spring 2018

#### Advanced Analog Integrated Circuits Lecture 2: MOS Transistor Models



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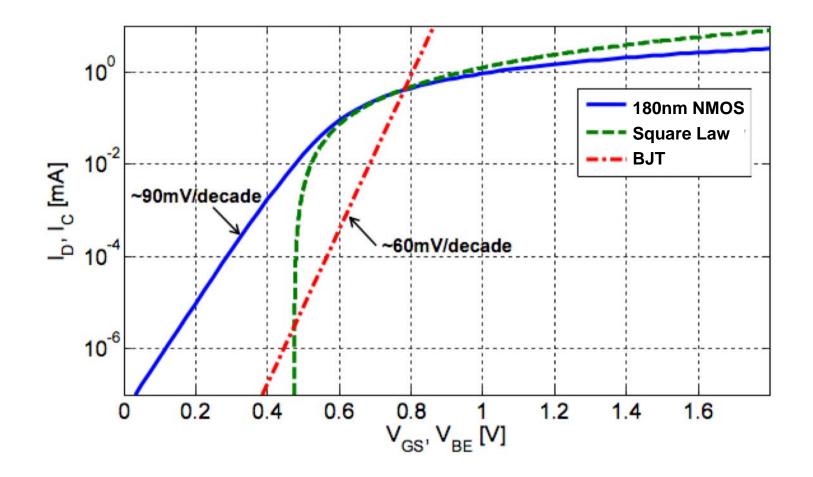
### **Square Law Model?**

$$I_{D,sat} = \frac{1}{2} \cdot \mu_n \cdot C_{ox} \cdot \frac{W}{L} \cdot \left(V_{GS} - V_{th}\right)^2$$

#### • Assumptions made to come up with this model:

- Charge density determined only by vertical field
- Drift velocity set only by lateral field
- Neglects diffusion currents ("magic" Vth)
- Constant mobility
- And about 10<sup>2</sup> 10<sup>3</sup> more parameters in a real SPICE model...

# Graphically



[B. Murmann]

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# **Better Hand Models?**

- There are better (less inaccurate) "hand" models out there
  - Velocity saturation
  - Alpha-power law
  - EKV
  - ...
- But all of them either (1) neglect certain effects or (2) are too unwieldy to be useful for hand analysis
  - This is particularly true if you want to say anything about r<sub>o</sub> (which we do typically care about in analog)

# Taking a Step Back

- Reminder: the model you use should be tailored to the question you are trying to answer
- "Hand" models are good for building intuition, and to a lesser extent, checking reasonableness of simulation results
- <u>Simulation</u> models are the ones you will have to use to "sign off" on your design
  - So our design methodology should be using the results from the full simulation models too

# **Basic Small Signal Transistor Model** (for Design)

# Biasing...

- In quadratic model,  $V_{od} = (V_{GS} V_{TH})$  told us a lot about important biasing tradeoffs:
  - $g_m = 2*I_D/V_{od}$
  - $r_o$  "large" for  $V_{DS} > V_{od}$ 
    - "Boundary between saturation and triode"

• 
$$\omega_{\rm T} = g_{\rm m}/C_{\rm gg} \propto V_{\rm od}$$

- But real transistors clearly aren't quadratic
  - And even worse, there is no way to actually measure V<sub>od</sub>
- Idea: work with a new (measurable) transistor
  FoM inspired by V<sub>od</sub>...

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# Transistor FoM #1: V\* (g<sub>m</sub>/I<sub>D</sub>)

• Define:

$$V^* = \frac{2I_D}{g_m} \qquad \Leftrightarrow \qquad \frac{g_m}{I_D} = \frac{2}{V^*}$$

e.g. V<sup>\*</sup> = 200mV 
$$\rightarrow$$
 g<sub>m</sub>/I<sub>D</sub> = 10 V<sup>-1</sup>

- Inspired by the fact that  $V^* = V_{od}$  for square law
- Devices definitely not square law, but can measure V\*
  - It will (by definition) set current efficiency
  - And (approximately) give you insight in to other parameters (r<sub>o</sub>,  $\omega_T$ , etc.)

## **Simplest Possible Usage of V\***

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#### **"Best" Possible V\*?**

# **Tradeoff for Low V\***

# Transistor FoM #2: ω<sub>T</sub>

- Reminder:  $\omega_T$  defined by  $||i_g(\omega_T)|| = ||i_d(\omega_T)||$ 
  - Measureable both in simulation and in hardware
  - In our simplified small-signal model,  $\omega_T = g_m/C_{gg}$ 
    - (C<sub>dd</sub> usually some fixed multiple relative to C<sub>gg</sub>, so  $\omega_T$  is a good FoM to capture this too.)
- Lower V\* results in better current efficiency, but lower  $\omega_{\text{T}}$ 
  - Best balance depends on transistor characteristics, desired gain-bandwidth
  - More on that next lecture

# What About L?

• How does transistor L affect V\*?

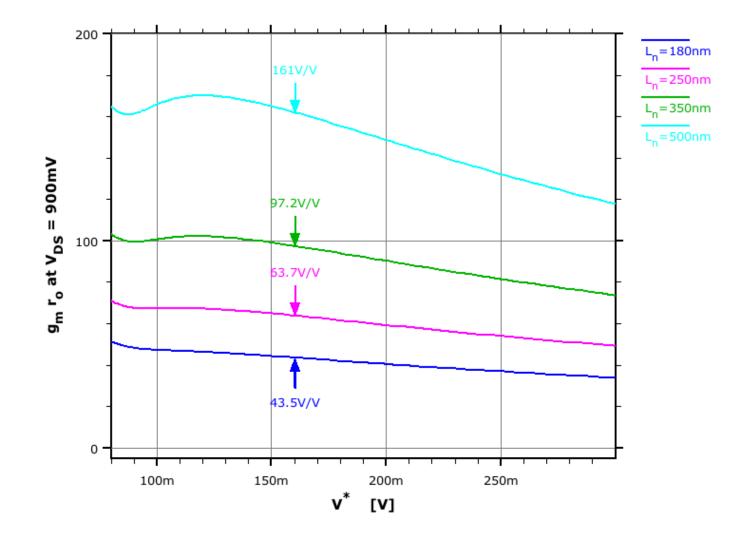
• How does transistor L affect  $\omega_T$ ?

# Transistor FoM #3: a<sub>v0</sub>

- Most of the time you don't actually care about value of r<sub>o</sub> itself
  - Just care about how it impacts circuit-level specifications
  - Most commonly, gain (A<sub>V</sub>)
- So, often use intrinsic gain  $a_{v0} = g_m^* r_o$  instead
  - Still measurable (from I-V curves) in both simulation and hardware

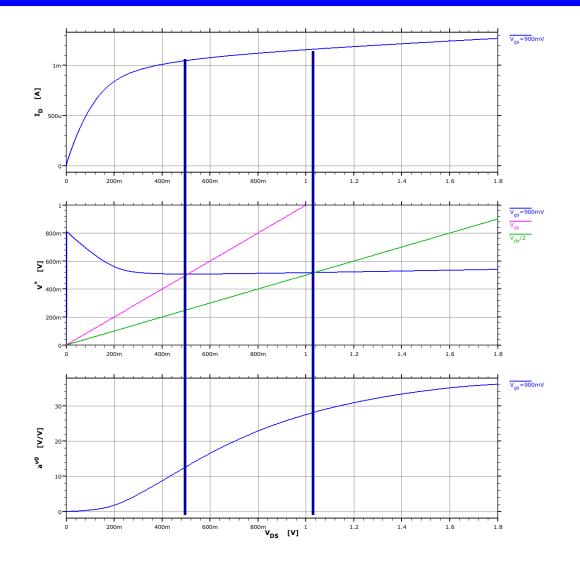
# Example Usage of $a_{v0}$

## Intrinsic Gain vs. L



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# Intrinsic Gain vs. V<sub>DS</sub>



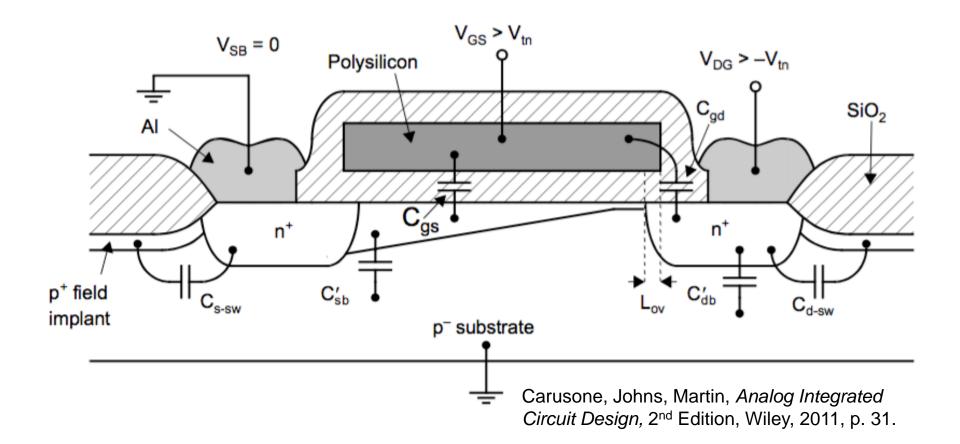
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### Loose End #1

- Talked about transistors so far as if they all have the same FoMs for given W, L, V<sub>GS</sub>, V<sub>DS</sub>, ...
- If you have 5 billion transistors on a single chip, do you think all of those transistors behave exactly the same?
- If you ship 100 million chips, do you think all of those chips will have the same specifications?

#### **Process Corners**

#### Loose End #2

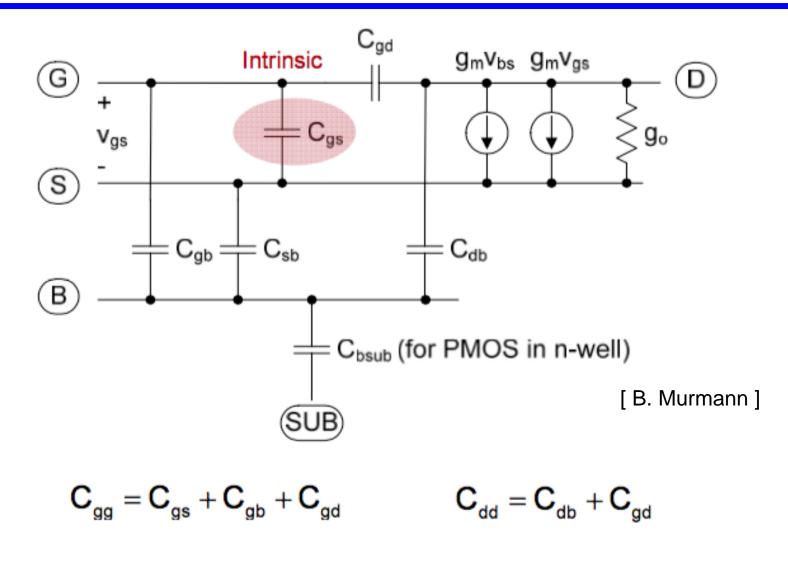


# **Small Signal Capacitances**

	Subthreshold	Triode	Saturation
C <sub>GS</sub>	C <sub>ol</sub>	C <sub>GC</sub> /2 + C <sub>ol</sub>	2/3 C <sub>GC</sub> + C <sub>ol</sub>
C <sub>GD</sub>	C <sub>ol</sub>	$C_{GC}/2 + C_{ol}$	C <sub>ol</sub>
C <sub>GB</sub>	C <sub>GC</sub>    C <sub>CB</sub>	0	0
C <sub>SB</sub>	C <sub>jSB</sub>	C <sub>jsB</sub> + C <sub>CB</sub> /2	C <sub>jsB</sub> + 2/3 C <sub>CB</sub>
C <sub>DB</sub>	C <sub>jDB</sub>	C <sub>jDB</sub> + C <sub>CB</sub> /2	C <sub>jDB</sub>

$$C_{GC} = C_{ox}WL$$
$$C_{CB} = \frac{\mathcal{E}_{Si}}{x_d}WL$$

# "Complete" Small Signal Model

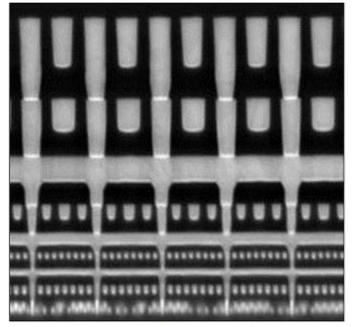


## **To Make Matters Worse...**

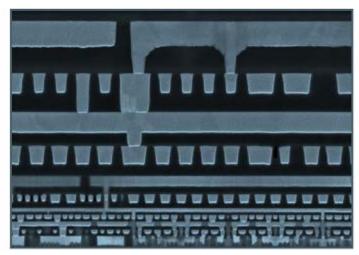
#### Interconnects

#### 22 nm Process

#### 14 nm Process



80 nm minimum pitch



52 nm (0.65x) minimum pitch

Image from Intel/www.legitreviews.com

#### "More Complete" Small Signal Model

#### So What Do We Do?

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# Final Note on Simplified Small Signal Model